

- 24 -

CLAIMS

1. A cleaning method for cleaning at least part of an ultrapure water supply system having an ultrapure water production apparatus connected to a point of use of
5 ultrapure water via a passage, comprising the steps of:

(a) changing surface potential of fine particles present in the at least part of the ultrapure water supply system; and

(b) discharging the fine particles from the at least
10 part of the ultrapure water supply system to outside.

2. The cleaning method according to claim 1, wherein in said step (a), the fine particles are made to contact with a basic solution or a solution of surfactant.

3. The cleaning method according to claim 1, wherein
15 in said step (a), the surface potential of the fine particles is changed and also physical force is applied to the fine particles.

4. The cleaning method according to claim 3, wherein in said step (a), a basic solution or a solution of
20 surfactant is caused to flow through the at least part of the ultrapure water supply system at a flow velocity of 0.5 m/sec to 2.0 m/sec.

5. The cleaning method according to claim 3, wherein in said step (a), with a basic solution or a solution of
25 surfactant kept in contact with the at least part of the ultrapure water supply system, the solution is applied with small-amplitude vibration.

6. The cleaning method according to ^{claim 2} any one of claims 2, 4 and 5, wherein the basic solution is an aqueous
30 solution of ammonia or ammonium salt, or an aqueous solution of alkali metal hydroxide, or a mixture of the aqueous solution of ammonia or ammonium salt and the aqueous solution of alkali metal hydroxide.

- 25 -

7. The cleaning method according to ^{claim 2} any one of claims 2, 4 and 5, wherein the basic solution is pure water or ultrapure water in which alkaline gas is dissolved.